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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/724,454	11/28/2003	Sang H. Ahn	008472/DSM/BCVD	9910	
7	590 05/31/2005		EXAMINER		
PATENT COUNSEL APPLIED MATERIALS, INC.			CHACKO DAVIS, DABORAH		
Legal Affairs I	- ,	ART UNIT PAPER NUMBER		PAPER NUMBER	
P.O. BOX 450A			1756		
Santa Clara, CA 95052		·	DATE MAILED: 05/31/2009	DATE MAILED: 05/31/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

		·	$\underline{}$			
	Application No.	Applicant(s)				
	10/724,454	AHN ET AL.				
Office Action Summary	Examiner	Art Unit				
	Daborah Chacko-Davis	1756				
The MAILING DATE of this communication ap	ppears on the cover sheet with the c	correspondence address				
A SHORTENED STATUTORY PERIOD FOR REPI THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a report of the period for reply specified above, the maximum statutory, erious failure to reply within the set or extended period for reply will, by status Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, may a reply be tir ply within the statutory minimum of thirty (30) day d will apply and will expire SIX (6) MONTHS from te, cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication (D) (35 U.S.C. § 133).	1.			
Status						
1)⊠ Responsive to communication(s) filed on 18 /	<u> April 2005</u> .					
2a) ☐ This action is FINAL. 2b) ☑ Th	is action is non-final.					
	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims						
4) Claim(s) 1-40 is/are pending in the application 4a) Of the above claim(s) 1-29,39 and 40 is/a 5) Claim(s) is/are allowed. 6) Claim(s) 30-38 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/	re withdrawn from consideration.					
Application Papers						
9)☐ The specification is objected to by the Examin	er.					
0) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the E		•	i) .			
Priority under 35 U.S.C. § 119			1			
12) Acknowledgment is made of a claim for foreig a) All b) Some * c) None of: 1. Certified copies of the priority documer 2. Certified copies of the priority documer 3. Copies of the certified copies of the priority application from the International Burea * See the attached detailed Office action for a list	nts have been received. Its have been received in Applicationity documents have been received in Applicationity documents have been received in Applicationity documents have been received in Application (PCT Rule 17.2(a)).	ion No ed in this National Stage				
Attachment(s)						
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date 12/03. 	4) Interview Summary Paper No(s)/Mail Do 5) Notice of Informal F 6) Other:					

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DETAILED ACTION

Election/Restrictions

- 1. Applicant's election without traverse of Group II, claims 30-38, in the reply filed on April 18, 2005, is acknowledged.
- 2. Claims 1-29, and 39-40, are withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected invention, there being no allowable generic or linking claim. Election was made **without** traverse in the reply filed on April 18, 2005.

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 4. Claims 30-38, are rejected under 35 U.S.C. 102(e) as being anticipated by U.S. Patent Application Publication No. 2005/0100683 (Fukiage et al).

Fukiage, in [0042], and [0069], disclose a method of reducing photoresist poisoning (reducing photoresist footing) in a chemically amplified photoresist (CAR photoresist produces acid upon exposure) by performing a plasma treatment on the underlying surface of the substrate (substrate coated with a TERA layer is plasma

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treated, controlling the composition of the TERA layer) (claim 30). Fukiage, in [0069], and [0070], discloses that the plasma process performed on the underlying layer (layer beneath the photoresist) uses an RF source that operates in a power range, and operates in a frequency range (more than one frequency) (claim 31). Fukiage, in [0037], [0046], [0049], [0053], [0058], [0061], [0069], [0084], discloses that the substrate underlying the photoresist is a dielectric ARC (DARC) (see figure 2C, references 230, 240, and 250), wherein the DARC is either a silicon-containing antireflecting coating (inorganic, silicon precursor) or an organic DARC, and that the plasma process performed on the antireflective coating (TERA) uses a hydrogen containing gas and/or a helium gas (claims 32-38).

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Conclusion

5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Daborah Chacko-Davis whose telephone number is (571) 272-1380. The examiner can normally be reached on M-F 9:30 - 6:00. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark F Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For

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more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

dcd MD

May 25, 2005

JOHN A. MCPHERSON PRIMARY EXAMINER Page 4